

**METHOD FOR SLOWING DOWN DOPANT-ENHANCED
DIFFUSION SUBSTRATES AND DEVICES FABRICATED
THEREFROM**

ABSTRACT OF THE DISCLOSURE

5 A method (and resulting structure) of forming a semiconductor device, includes implanting, on a substrate, a dopant and at least one species, annealing the substrate, the at least one species retarding a diffusion of the dopant during the annealing of the substrate.